

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	("6635155").PN.	US-PGPUB; USPAT	OR	OFF	2007/08/26 15:06
S2	4	(("4851095") or ("6103320") or ("5082546") or ("5169509")).PN.	US-PGPUB; USPAT	OR	OFF	2007/04/18 15:27
S3	0	jp-8511830-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/04/18 15:28
S4	1	jp-08511830-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/04/18 15:28
S5	2	jp-11256327-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/04/18 15:28
S6	7	"204".clas. and magnetron and cathode and (partition or separator or divider) and shutter and sputter and (ac or alternating current) and (dc or direct current)	US-PGPUB; USPAT	ADJ	ON	2007/04/19 13:29
S7	18	"204".clas. and magnetron and cathode and (partition or separator or divider) and shutter and sputter	US-PGPUB; USPAT	ADJ	ON	2007/04/25 17:29
S8	0	Rauschnabel.in. and (method for applying a wear protection system)	US-PGPUB; USPAT	ADJ	ON	2007/04/25 12:49
S9	7	Rauschnabel.in.	US-PGPUB; USPAT	ADJ	ON	2007/04/25 12:53
S10	10	(("4619865") or ("4830873") or ("4883686") or ("5002794") or ("5242740") or ("5363400") or ("5837331") or ("5846608") or ("6044792") or ("6287642")).PN.	US-PGPUB; USPAT	OR	OFF	2007/04/25 12:54
S11	1	us-6613393-\$ did.	DERWENT	ADJ	ON	2007/04/25 17:29
S12	1	2000-040068.NRAN.	DERWENT	ADJ	ON	2007/04/25 17:30
S13	4	(("6726805") or ("7175713") or ("6186090") or ("5582866")).PN.	US-PGPUB; USPAT	OR	OFF	2007/08/26 16:45
S14	64	chiang.in. and (applied materials).as.	US-PGPUB; USPAT	ADJ	ON	2007/08/26 16:46
S15	38	chiang.in. and (applied materials).as. and sputter	US-PGPUB; USPAT	ADJ	ON	2007/08/26 16:46

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S16	33	chiang.in. and (applied materials). as. and sputter and vacuum	US-PGPUB; USPAT	ADJ	ON	2007/08/26 16:46
S17	22	chiang.in. and (applied materials). as. and sputter and vacuum and (pvd or physical vapor depositon) and (cvd or chemical vapor depositoon)	US-PGPUB; USPAT	ADJ	ON	2007/08/26 16:46
S18	22	chiang.in. and (applied materials). as. and sputter and vacuum and (pvd or physical vapor depositon) and (cvd or chemical vapor depositon)	US-PGPUB; USPAT	ADJ	ON	2007/08/26 16:46
S19	27	chiang.in. and (applied materials). as. and sputter and vacuum and (pvd or physical vapor deposition) and (cvd or chemical vapor deposition)	US-PGPUB; USPAT	ADJ	ON	2007/08/26 16:47
S20	2	("5154810" "6338777").PN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2007/12/18 18:28
S21	0	jp-200200982-\$ did.	JPO	ADJ	ON	2007/12/18 18:29
S22	0	jp-0200982-\$ did.	JPO	ADJ	ON	2007/12/18 18:29
S23	0	jp-200982-\$ did.	JPO	ADJ	ON	2007/12/18 18:30
S24	1	jp-02200982-\$ did.	EPO; JPO; DERWENT	ADJ	ON	2007/12/18 18:31
S25	2	jp-2002200982-\$ did.	EPO; JPO; DERWENT	ADJ	ON	2007/12/18 18:30
S26	2	jp-2001031004-\$ did.	EPO; JPO; DERWENT	ADJ	ON	2007/12/18 18:31
S27	1	jp-01031004-\$ did.	EPO; JPO; DERWENT	ADJ	ON	2007/12/18 18:33
S28	0	magnetron and (shutter near simultaneous\$)	EPO; JPO; DERWENT	ADJ	ON	2007/12/18 18:34
S29	4	magnetron and (shutter with simultaneous\$)	EPO; JPO; DERWENT	ADJ	ON	2007/12/18 18:35
S30	79	magnetron and (shutter with simultaneous\$)	US-PGPUB; USPAT; JPO	ADJ	ON	2007/12/18 18:35
S31	75	magnetron and (shutter with simultaneous\$)	US-PGPUB; USPAT	ADJ	ON	2007/12/18 18:50
S32	37	magnetron and (shutter with simultaneous\$)	USPAT	ADJ	ON	2007/12/18 18:35
S33	38	magnetron and (shutter with simultaneous\$)	US-PGPUB	ADJ	ON	2007/12/18 18:50